

SESAME – Kickoff Meeting

University of Wuppertal

Frederic Braun / Dirk Lützenkirchen-Hecht

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SESAME: Working Plan - University of Wuppertal

Year 1

- Upgrade of the field emission setup and implementation of SEY measurements
- Setup of a dedicated SEY experiment
- Laser polishing optimization for thin films and multilayers
- Initial surface characterization

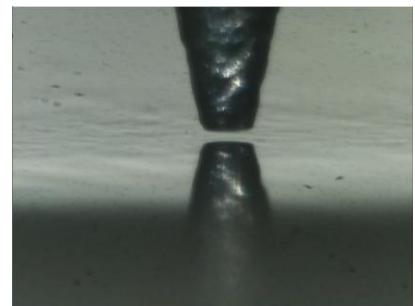
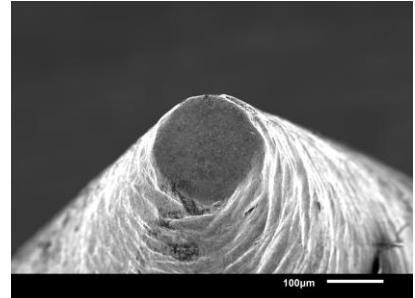
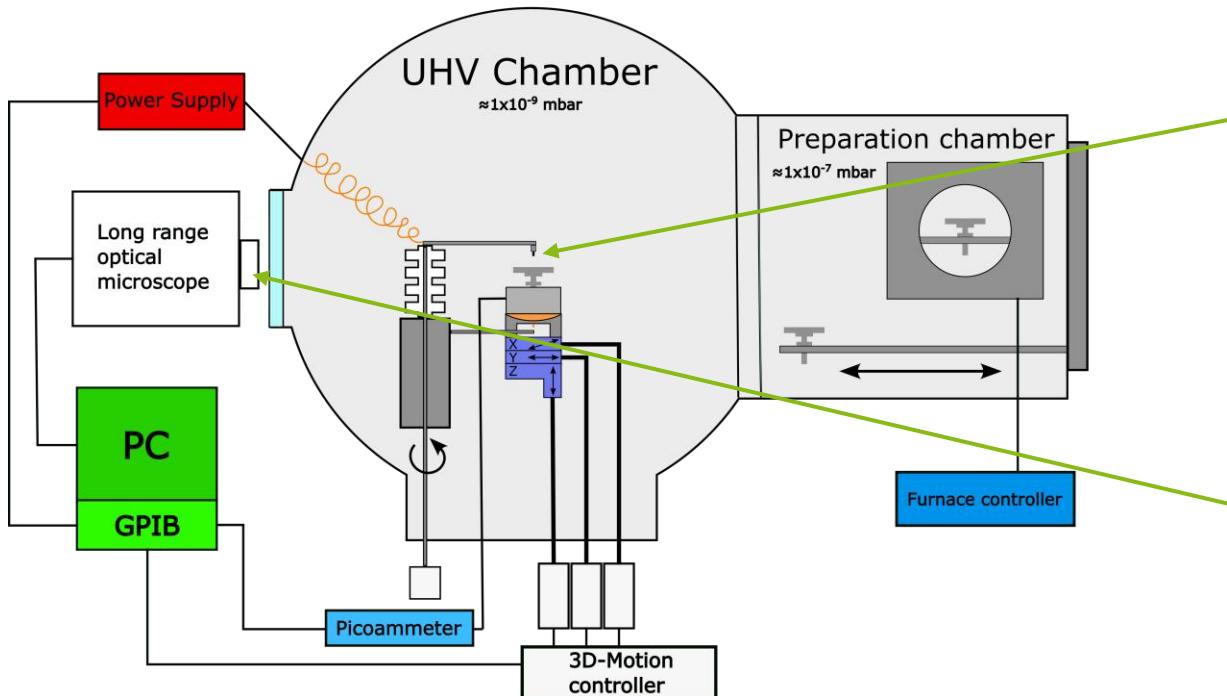
Year 2

- Systematic laser polishing studies
- Optimization for novel materials and complex multilayer systems

Year 3

- Correlation of surface preparation with accelerating field strength and SEY
- Modeling, publications and conference contributions

FESM

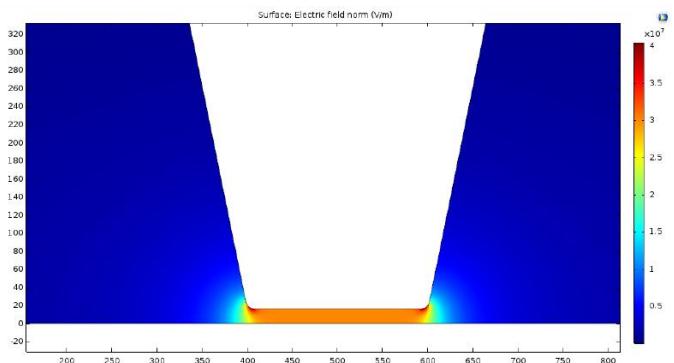
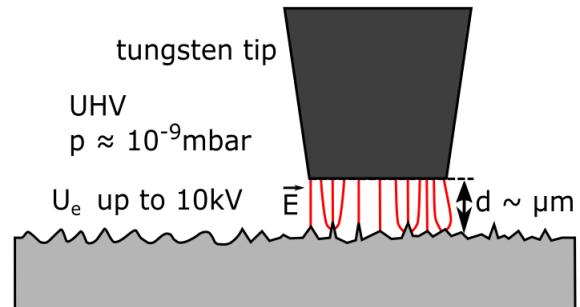


Working Principle

Current flows after Fowler-Nordheim-Equation

$$I(E) = \frac{AS\beta^2 E^2}{\Phi} \exp\left(-\frac{B\Phi^{\frac{3}{2}}}{\beta E}\right)$$

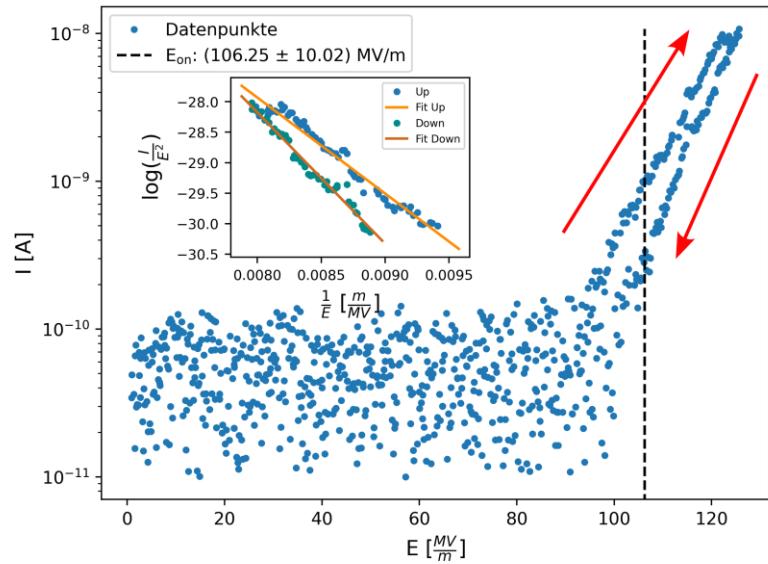
With A/B as material constants , Φ as work function, β as geometric field enhancement factor and S as area of effective emittance



- Truncated Tips with a diameter up to 1 mm
- No field enhancement of the tip
- β yields field enhancement of the surface under the tip

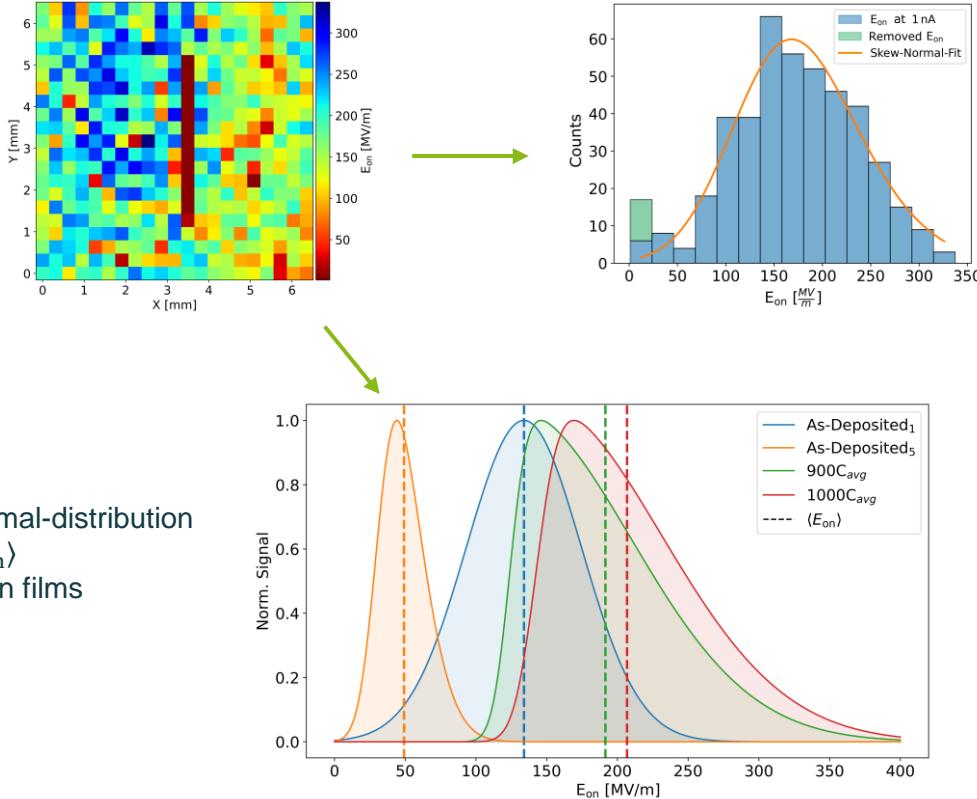
Current-Voltage-Curve (I-V-Curves)

- Increasing voltage until current is measured (Up)
- Decreasing voltage until 0 V (Down)
- With Sample-Tip-Distance
→ calculation of electrical field E
- Onset-field E_{on} defined at 1 nA
- Plotting and fitting of $\log\left(\frac{I}{E^2}\right)$ vs. $\frac{1}{E}$ yields β , S and Φ

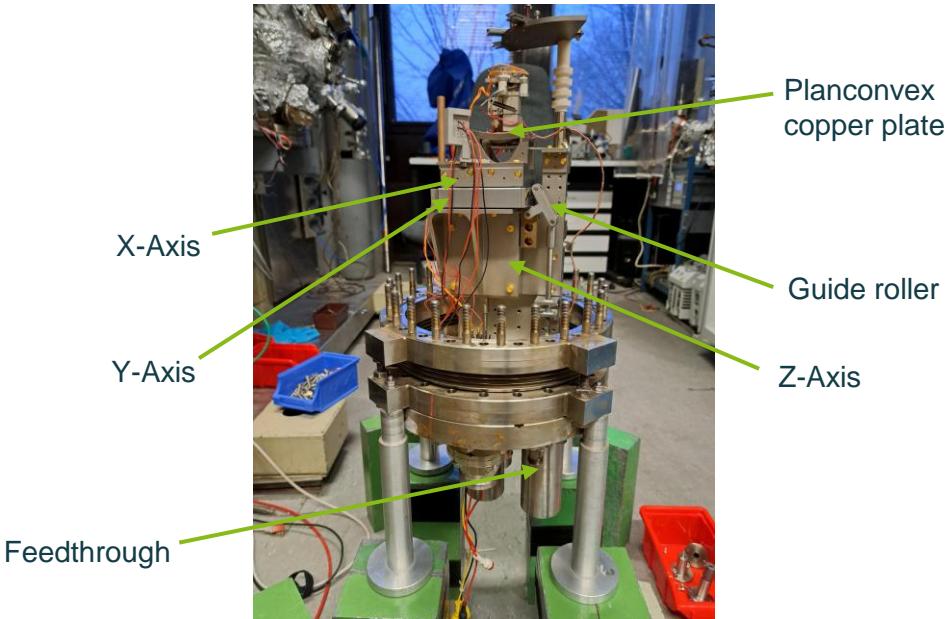


Constant Current Maps

- Mapping I-V-Curves over an Area
→ Creating Constant Current Map (CCMap)
- CCMaps show the onset-field distribution
- Reveals influence of
 - Topography
 - Chemical composition
- Plotting as histograms and fitting with skew-normal-distribution
 - Yields expected onset-field strength $\langle E_{on} \rangle$
- Example: as-deposited and annealed NbTiN thin films



Upgrading the FESM

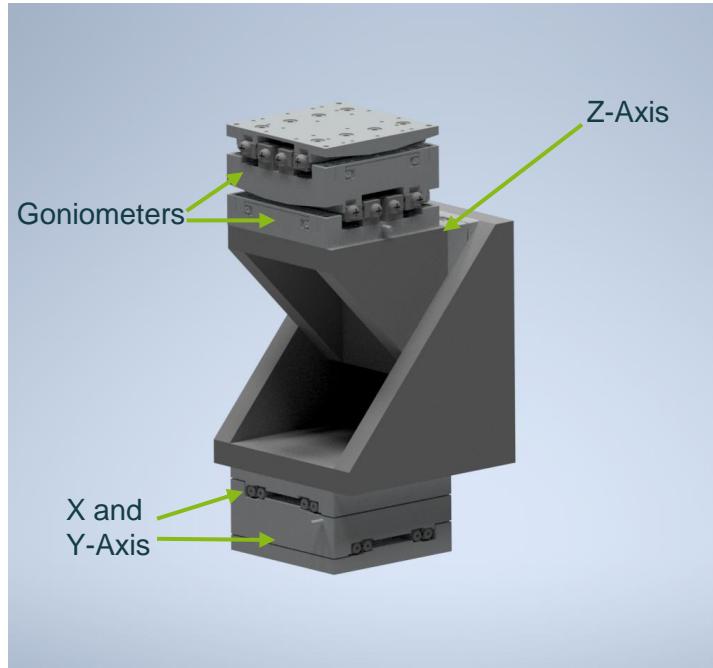


- Mechanical XYZ-Stage is old and worn
- Mechanical feedthroughs and guide rollers decrease positioning accuracy
 - Up to $\pm 1 \mu\text{m}$ for X,Y,Z directions
- Sample leveling via plan convex copper plate
 - Manual and time-consuming alignment
 - Limited reproducibility
 - Additional leveling-induced uncertainty

→ Redesign of the XYZ-Stage and sample alignment

Upgrading the FESM

- Goal: minimize positioning uncertainty and improve sample alignment
- Piezo-Linear-Stages for X, Y and Z directions
 - Improving positioning accuracy to 40 nm
 - Travel up to 31 mm
- Two Piezo-Goniometer-Stages
 - Repeatable positioning of 100 μ °
 - Travel up to 5 °
 - Software controlled
 - Allows for automatic alignment
- Delivery date expected in April
- FESM measurements possible until April
- Out of commission from April until approx. June



Conceptual CAD layout



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